

APPLICATION DATA SHEET

Electronic Version v14

Stylesheet Version v14.0

Title of Invention	METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI ON SIGE SUBSTRATE
Application Type : regular, utility Attorney Docket Number : FIS920030183US1	
Correspondence address: Customer Number: 29625 	
Inventors Information: <u>Inventor 1:</u> Applicant Authority Type: Inventor Citizenship: US Given Name: Dureseti Family Name: Chidambarao Residence: City of Residence: Weston State of Residence: CT Country of Residence: US Address-1 of Mailing Address: 29 Old Mill Road Address-2 of Mailing Address: City of Mailing Address: Weston State of Mailing Address: CT Postal Code of Mailing Address: 06883 Country of Mailing Address: US Phone: Fax: E-mail: <u>Inventor 2:</u> Applicant Authority Type: Inventor Citizenship: TR Given Name: Omer Middle Name: H. Family Name: Dokumaci	

Residence:

City of Residence: Wappingers Falls
State of Residence: NY
Country of Residence: US
Address-1 of Mailing Address: 32E Winthrop Court

Address-2 of Mailing Address:

City of Mailing Address: Wappingers Falls
State of Mailing Address: NY
Postal Code of Mailing Address: 12590
Country of Mailing Address: US

Phone:**Fax:****E-mail:****Publication Information:**

Suggested Figure for Publication - 1
Suggested Classification -
Suggested Technology Center -
Total Number of Drawing Sheets - 2

Assignee 1:

Organization Name: International Business Machines Corporation
Address-1 of Mailing Address: New Orchard Drive
Address-2 of Mailing Address:
City of Mailing Address: Armonk
State of Mailing Address: NY
Postal Code of Mailing Address: 10504
Country of Mailing Address: US
Phone:
Fax:
E-mail: